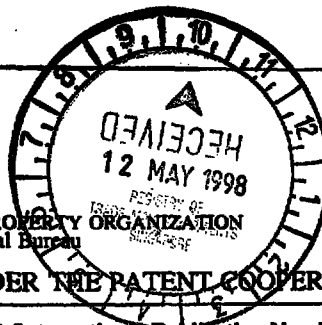


980 2050-6

**PCT**WORLD INTELLECTUAL PROPERTY ORGANIZATION
International Bureau

INTERNATIONAL APPLICATION PUBLISHED UNDER THE PATENT COOPERATION TREATY (PCT)

(51) International Patent Classification ⁶: C08G 8/08, G03F 7/032	A1	(11) International Publication Number: WO 97/11100 (43) International Publication Date: 27 March 1997 (27.03.97)
(21) International Application Number: PCT/US96/14946 (22) International Filing Date: 18 September 1996 (18.09.96) (30) Priority Data: 08/530,847 20 September 1995 (20.09.95) US (71) Applicant: HOECHST CELANESE CORPORATION [US/US]; Route 202-206 North, Somerville, NJ 08876 (US). (72) Inventors: RAHMAN, M., Dalil; 62 Concord Ridge Road, Flemington, NJ 08822 (US). AUBIN, Daniel, P.; 202 Congdon Road, P.O. Box 276, Voluntown, CT 06384 (US). KHANNA, Dinesh, N.; Seven Sutton Farm Road, Flemington, NJ 08822 (US). DIXIT, Sunit, S.; 50 Copper Penny Road, Flemington, NY 08822 (US). (74) Agents: SAYKO, Andrew, F., Jr. et al.; Hoechst Celanese Corporation, 70 Meister Avenue, Somerville, NJ 08876 (US).		(81) Designated States: CN, JP, KR, SG, European patent (AT, BE, CH, DE, DK, ES, FI, FR, GB, GR, IE, IT, LU, MC, NL, PT, SE). Published <i>With international search report. Before the expiration of the time limit for amending the claims and to be republished in the event of the receipt of amendments.</i>
(54) Title: FRACTIONATION OF PHENOL FORMALDEHYDE CONDENSATE AND PHOTORESIST COMPOSITIONS PRODUCED THEREFROM (57) Abstract A process for producing a water insoluble, aqueous alkali soluble, film forming novolak resin having low metal ions, made by the fractionation of a phenol formaldehyde condensation product, a process for producing a resin, a photoresist composition of superior quality containing such novolak resin, and a method for producing a semiconductor device using such photoresist composition.		